

ABSTRACT OF THE DISCLOSURE

HIGH PURITY TUNGSTEN HEXACHLORIDE AND METHOD FOR MAKING SAME

Condensable metal halide materials, such as but not limited to tungsten chloride (WCl_6), can be used deposit films metal or metal containing films in a chemical vapor deposition (CVD) or atomic layer deposition process. Described herein are high purity compositions comprising condensable materials and methods to purify condensable materials. In one aspect, there is provided a composition comprising: tungsten hexachloride which is substantially free of at least one impurity and wherein the tungsten hexachloride comprises at least 90%, preferably 95 % and more preferably 99 % by weight or greater of a β - WCl_6 and 5% by weight or less of the α - WCl_6 as measured by X-ray diffraction.

(No drawing to be published)